

AMENDMENTS TO THE SPECIFICATION

Please replace the second paragraph on page 2 with the following amended paragraph:

The film forming apparatus according to the invention is characterized in that the apparatus comprises: a rotating unit ~~(1)~~ for rotating a substrate ~~(3)~~; and a film forming jig ~~(2)~~ which is to be placed on the substrate ~~(3)~~, and in a state where a film forming liquid ~~(4)~~ is supplied to contact with an outer periphery of the film forming jig ~~(2)~~, the rotation unit ~~(1)~~ rotates to form a film ~~(4A)~~.

Please replace the second and third paragraphs on page 3 with the following amended paragraphs:

The film forming jig ~~(2)~~ may have any one of a substantially cylindrical shape ~~(2)~~, a substantially conical shape ~~(22)~~, and a substantially truncated conical shape ~~(21, 23)~~.

The film forming method according to the invention is characterized in that the method comprises the steps of: placing a film forming jig ~~(2)~~ on a substrate ~~(3)~~; supplying film forming liquid ~~(4)~~ to be in contact with an outer periphery of the film forming jig ~~(2)~~; and rotating the substrate ~~(3)~~.

Please replace the first paragraph on page 4 with the following amended paragraph:

The film forming apparatus according to the invention is characterized in that the apparatus comprises: a rotating unit ~~(101)~~ for rotating a substrate ~~(103)~~; and a film forming liquid supplying device ~~(102)~~ for supplying film forming liquid ~~(104)~~ onto the substrate ~~(103)~~ during rotation of the rotating unit ~~(101)~~.

Please replace the third paragraph on page 4 with the following amended paragraph:

A non-film-forming region ~~(103a)~~ to which the film forming liquid is not applied may be disposed in the substrate ~~(103)~~, and the film forming liquid supplying device ~~(102)~~ may supply the film forming liquid ~~(104)~~ to a region outside the non-film-forming region ~~(103a)~~. In this case, the film forming liquid is supplied to the region outside the non-film-forming region, the film forming liquid is spread further outward by the centrifugal force due to the rotation of the substrate, and hence the film is formed in only the region outside the non-film-forming region.

Please replace the first through fourth paragraphs on page 5 with the following amended paragraphs:

The film forming liquid supplying device ~~(102)~~ may comprise a liquid reservoir ~~(131)~~ for storing the film forming liquid ~~(104)~~, and the film forming liquid ~~(104)~~ stored in the liquid reservoir ~~(131)~~ may be supplied onto the substrate ~~(103)~~ through a supply port ~~(132)~~ communicating with the liquid reservoir ~~(131)~~. For example, the supply port may be a slit or a nozzle.

The film forming liquid ~~(104)~~ may be supplied through the supply port ~~(133)~~ by applying an air pressure to the film forming liquid ~~(104)~~ stored in the liquid reservoir ~~(131)~~. In this case, the film forming liquid can be surely supplied without using, for example, a centrifugal force. The supplied amount of the film forming liquid can be controlled by adjusting the air pressure. The air pressure may be changed during the rotation of the rotating unit.

The liquid reservoir ~~(131)~~ may be rotatable together with the rotating unit ~~(101)~~.

The film forming liquid ~~(104)~~ may be supplied through the supply port ~~(133)~~ by applying a centrifugal force due to the rotation of the rotating unit ~~(201)~~ to the film forming liquid ~~(104)~~

stored in the liquid reservoir ~~(131)~~. In this case, the film forming liquid may be supplied by the centrifugal force without applying an air pressure to the liquid reservoir.

Please replace the first and second paragraphs on page 6 with the following amended paragraphs:

The substrate may be an optical disc substrate ~~(103)~~.

The film forming method according to the invention is characterized in that the method comprises the steps of supplying a film forming liquid ~~(104)~~ onto a substrate ~~(103)~~ while the substrate ~~(103)~~ is rotated.

Please replace the fourth paragraph on page 6 with the following amended paragraph:

A non-film-forming region ~~(103a)~~ to which the film forming liquid ~~(104)~~ is not applied may be disposed in the substrate ~~(103)~~, and the film forming liquid supplying device ~~(102)~~ may supply the film forming liquid to a region outside the non-film-forming region ~~(103a)~~. In this case, the film forming liquid is supplied to the region outside the non-film-forming region, the film forming liquid is spread further outward by the centrifugal force due to rotation of the substrate, and hence the film is formed in only the region outside the non-film-forming region.

Please replace the first through fourth paragraphs on page 7 with the following amended paragraphs:

The method may further comprise the steps of storing the film forming liquid ~~(104)~~ into a liquid reservoir ~~(131)~~, and, in the supplying step, the film forming liquid ~~(104)~~ stored in the liquid reservoir ~~(131)~~ is supplied onto the substrate ~~(103)~~ through a supply port ~~(132)~~

communicating with the liquid reservoir-(131). For example, the supply port may be a slit or a nozzle.

In the supplying step, the film forming liquid (104)-may be supplied through the supply port (132)-by applying an air pressure to the film forming liquid (104)-which is stored in the liquid reservoir-(131). In this case, the film forming liquid can be surely supplied without using, for example, a centrifugal force. The supplied amount of the film forming liquid can be controlled by adjusting the air pressure. The air pressure may be changed during the rotation of the rotating unit.

The liquid reservoir (131)-may be rotatable together with the rotating unit-(101).

A centrifugal force due to rotation of the rotating unit (201)-may be applied to the film forming liquid (104)-stored in the liquid reservoir, whereby the film forming liquid (104)-is supplied through the supply port-(133). In this case, the film forming liquid may be supplied by the centrifugal force without applying an air pressure to the liquid reservoir.

Please replace the first paragraph on page 8 with the following amended paragraph:

The substrate may be an optical disc substrate-(103).